

2008 VLSI Technology Short Course
TAPA I/II
**CMOS Logic – Technology Challenges for
the
Transition from 32nm to 22nm**

Monday, June 16, 8:10 a.m.

Organizers: Klaus Schroefer, Infineon Technologies
Satoshi Inaba, Toshiba Corporation
Digh Hisamoto, Hitachi Ltd.

- 8:10 a.m. Introduction**
K. Schroefer, Infineon Technologies
- 8:15 a.m. Lithography Solutions**
M. Colburn, IBM Corporation
- 9:25 a.m. FEOL Scaling, New Device Architectures
and Materials**
J. Kavalieros, Intel Corporation
- 10:35 a.m. Break**
- 10:50 Interconnect Scaling, Processes and Integration**
H.-J. Barth, Infineon Technologies
- 12:00 p.m. Lunch**
- 1:30 p.m. System on Chip – Key Aspects for MS/RF
Integration**
M. Huang, Freescale
- 2:40 p.m. Break**
- 2:55 p.m. Embedded Memory: SRAM**
Y. Kim, Samsung Electronics
- 4:05 p.m. Variability and DFM**
H. Yoshimura, Toshiba Corporation
- 5:15 p.m. Conclusion**